The background of the slide is a photograph of a modern building with a prominent dome, likely the Aachen Palace. In the foreground, there is a large fountain with multiple water jets. The image is semi-transparent, allowing the text to be clearly visible.

The enabling role of graphene in integrated optics

Daniel Schall

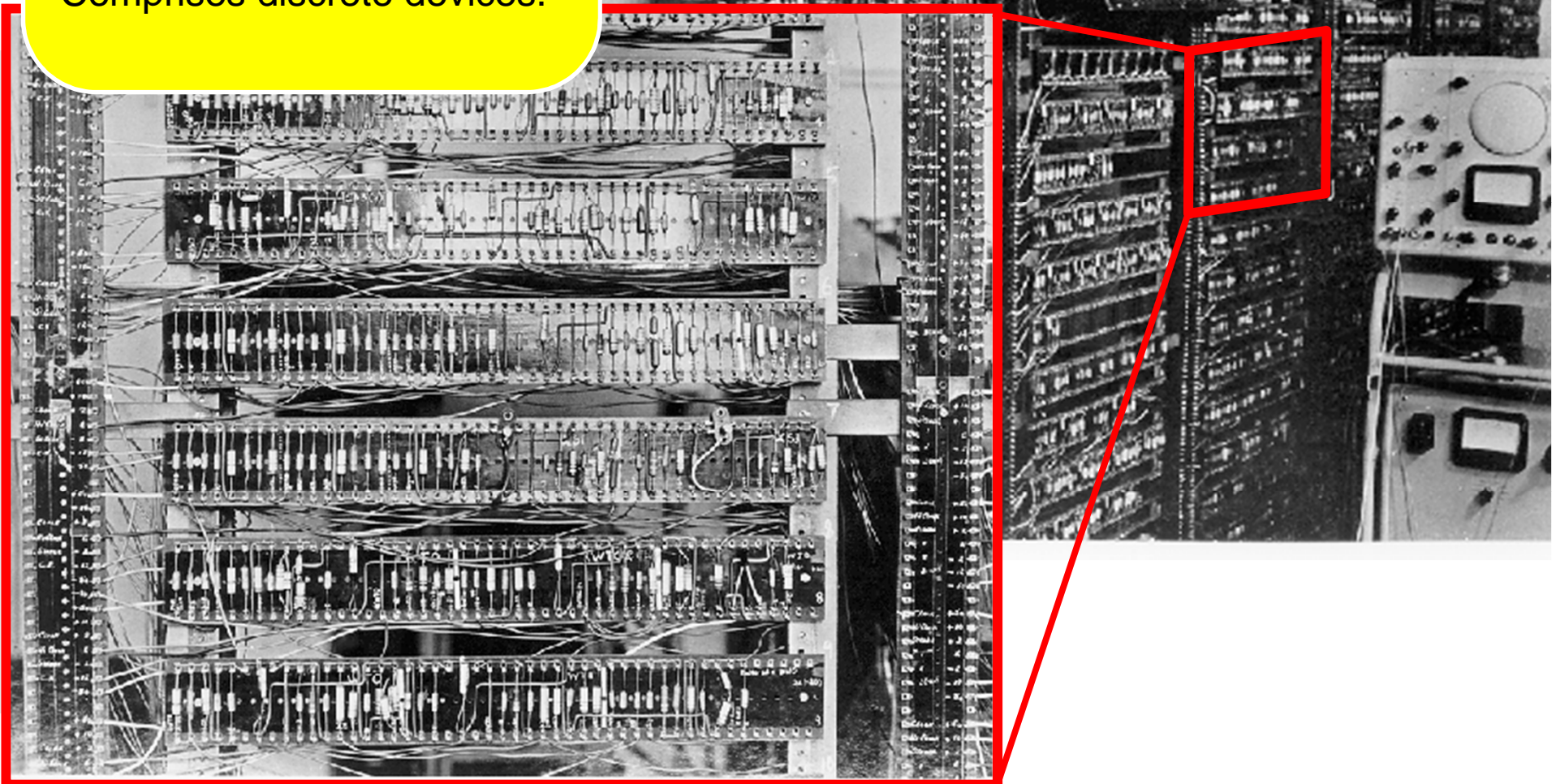
Advanced Microelectronic Center Aachen - AMO GmbH Germany

1953:

*Manchester University
Transistor Computer*

First computer with
transistors.

Comprises discrete devices.

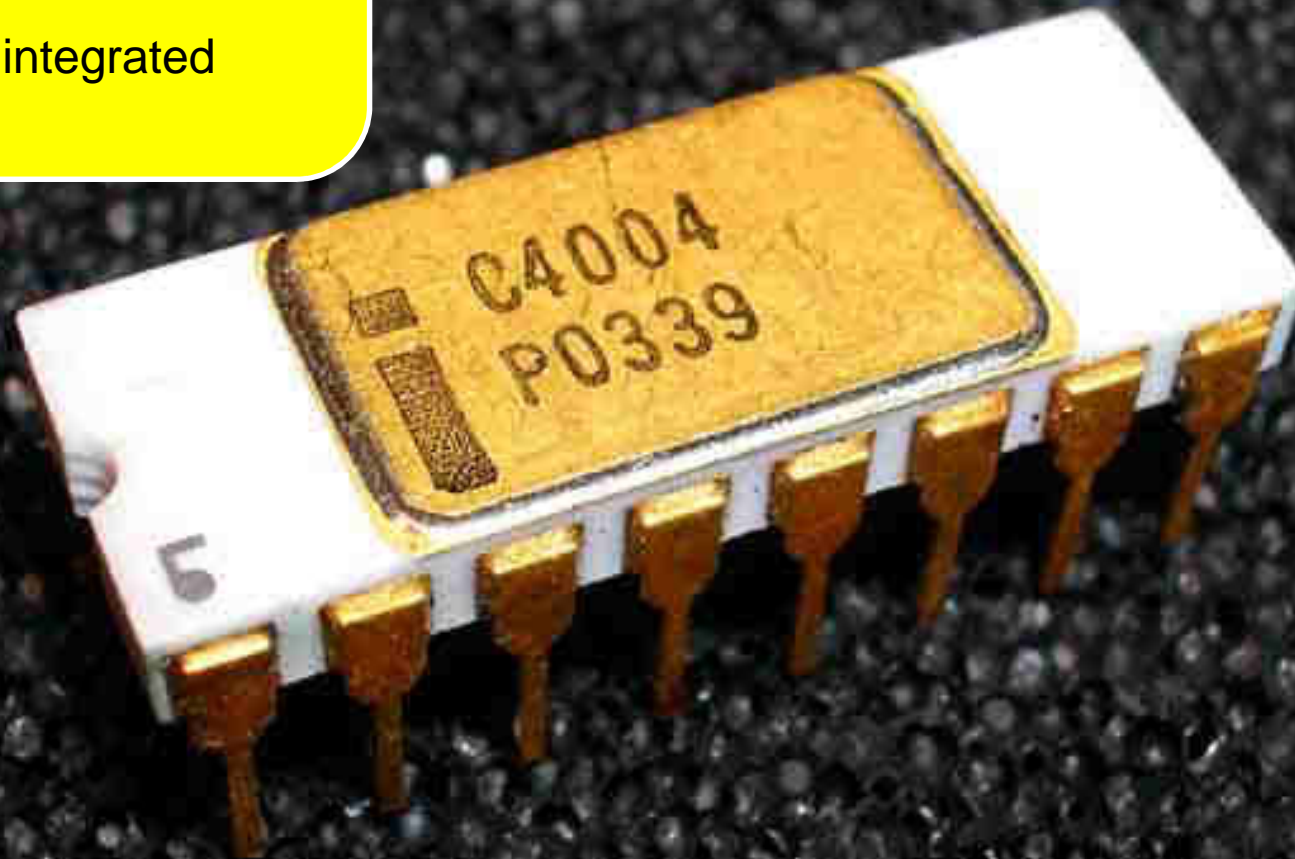


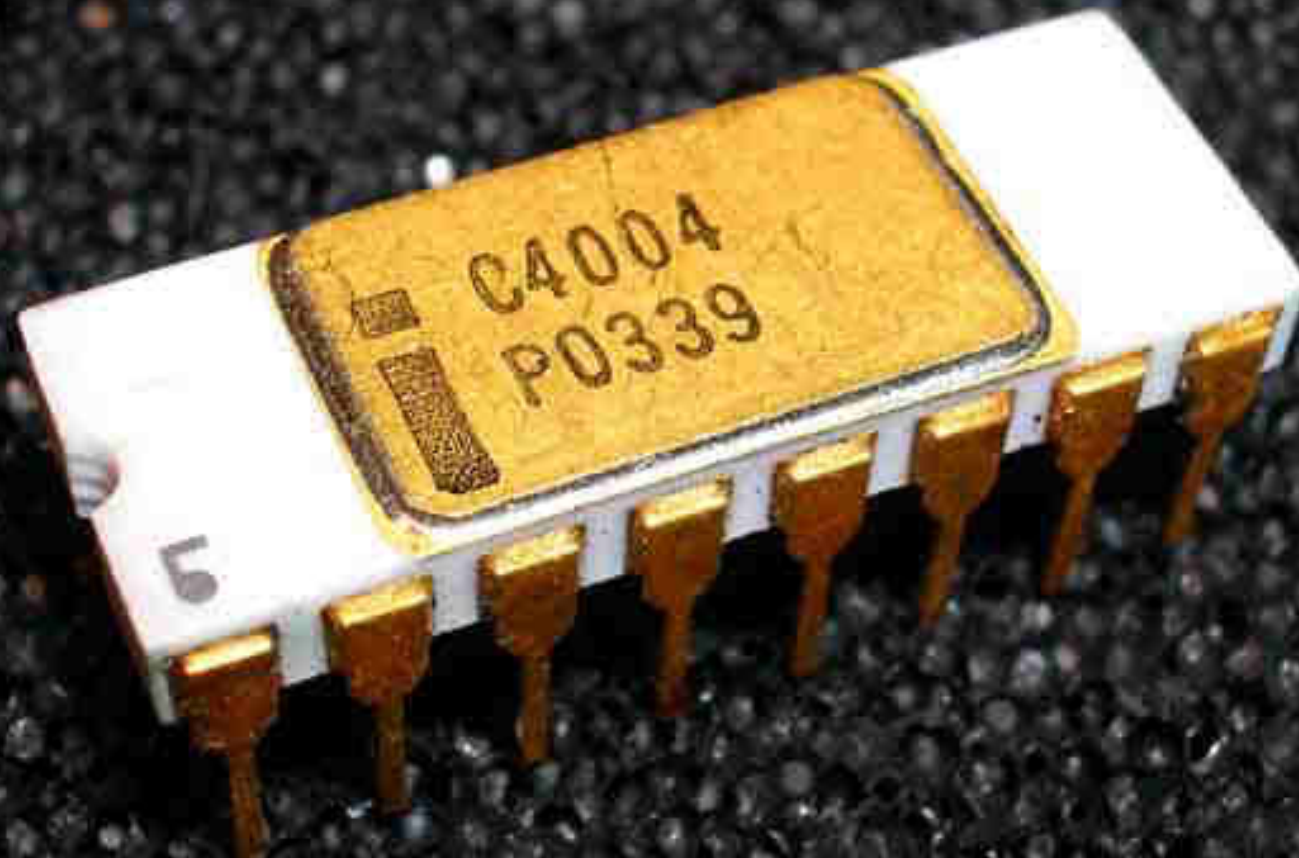
1970:

Intel 4004

First integrated processor.

Comprises integrated transistors.



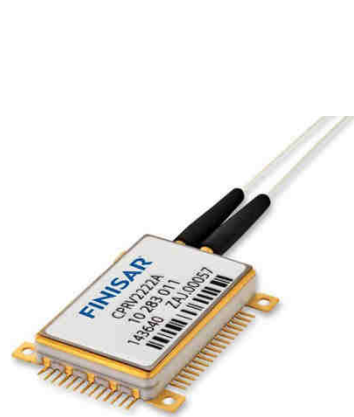


Paradigm shift in microelectronics.

2015:

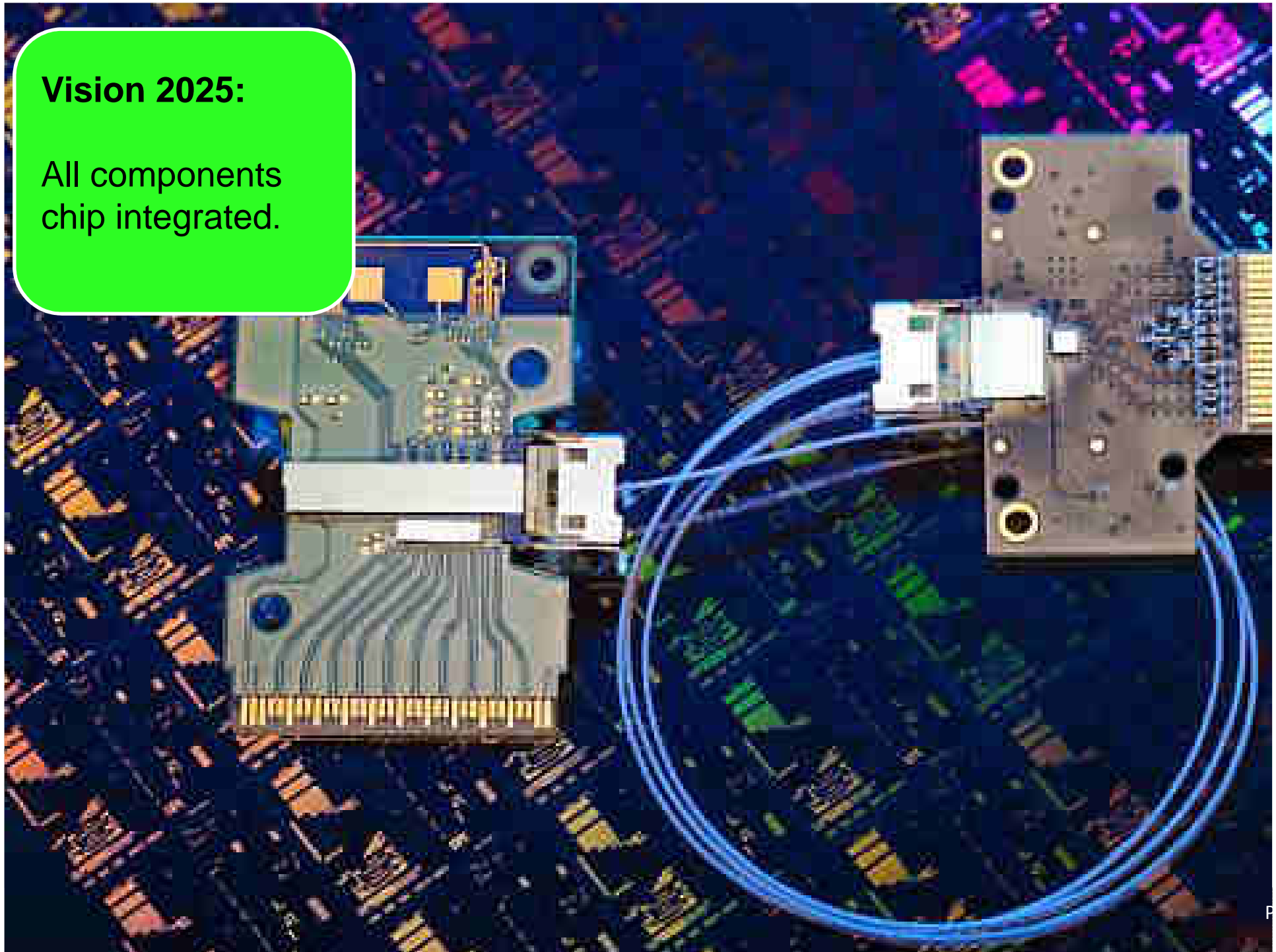
Cisco CRX 1
Carrier router system.

Comprises discrete
components.



Vision 2025:

All components
chip integrated.

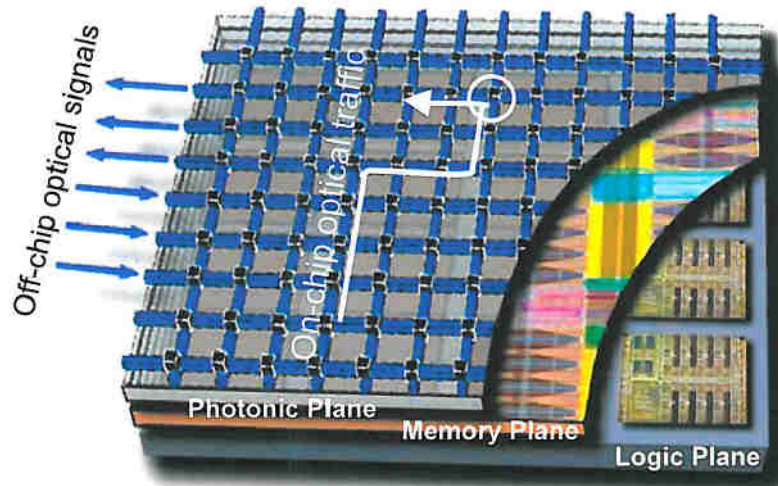


The image shows two optical modules, one on the left and one on the right, connected by several blue fiber optic cables. The background is a dense, colorful network of fiber optic cables, with some cables highlighted in red and green. The text "Paradigm shift in opto-electronics." is overlaid on a red rectangular background at the bottom center of the image.

Paradigm shift in opto-electronics.

Extension: Vision for 22 nm CMOS Convergence Optics / Electronics

Vision for 22nm CMOS (circa 2018) - 10 TFLOPs on a 3D chip



36 "Cell" chip (~300 cores)

System level study:
IBM, Columbia, Cornell, UCSB

Co-PIs:
Jeff Kash (IBM)
Keren Bergman (Columbia)
Yurii Vlasov (IBM)

Logic plane	~300 cores
Memory plane	~30GB eDRAM
Photonic plane	On-Chip Optical Network
	>70Tbps optical on-chip
	>70Tbps optical off-chip

Photonic layer is not only connecting various cores, but also routes the traffic

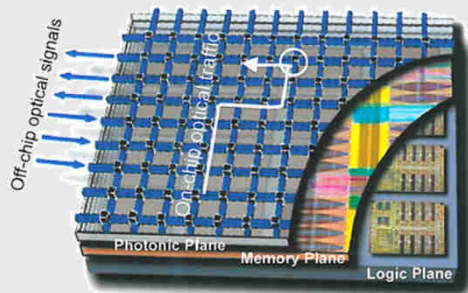
All future dates and specifications are estimations only. Subject to change without notice.



Current bottleneck: Detectors and modulators

Paradigm shift – Device requirements

Device requirements



Material must enable devices with:

- High bandwidth
- High sensitivity
- High extinction ratio
- Low energy consumption
- Low drive voltages
- Low insertion loss
- Small footprint

Technological requirements

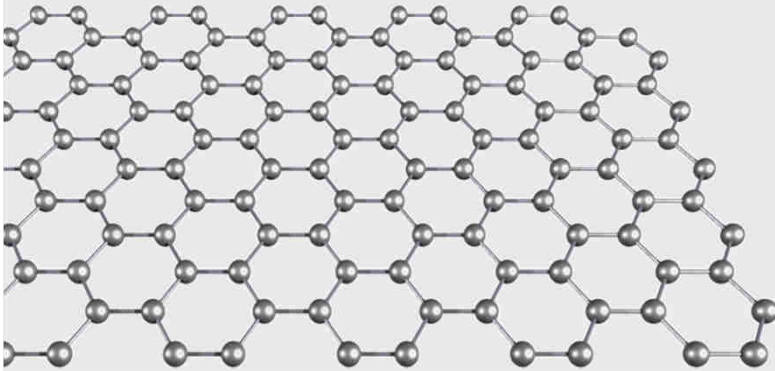
Manufacturing and integration:

- Manufacturing on large scale
- Integration possible
- Process compatibility

Can graphene meet the requirements?

Why graphene?

Intrinsic properties of graphene are promising:



- Ultra broadband interaction (IR-UV)
- High absorption
- High carrier mobility
- Fast relaxation of excited carriers
- Optical properties tunable by gating

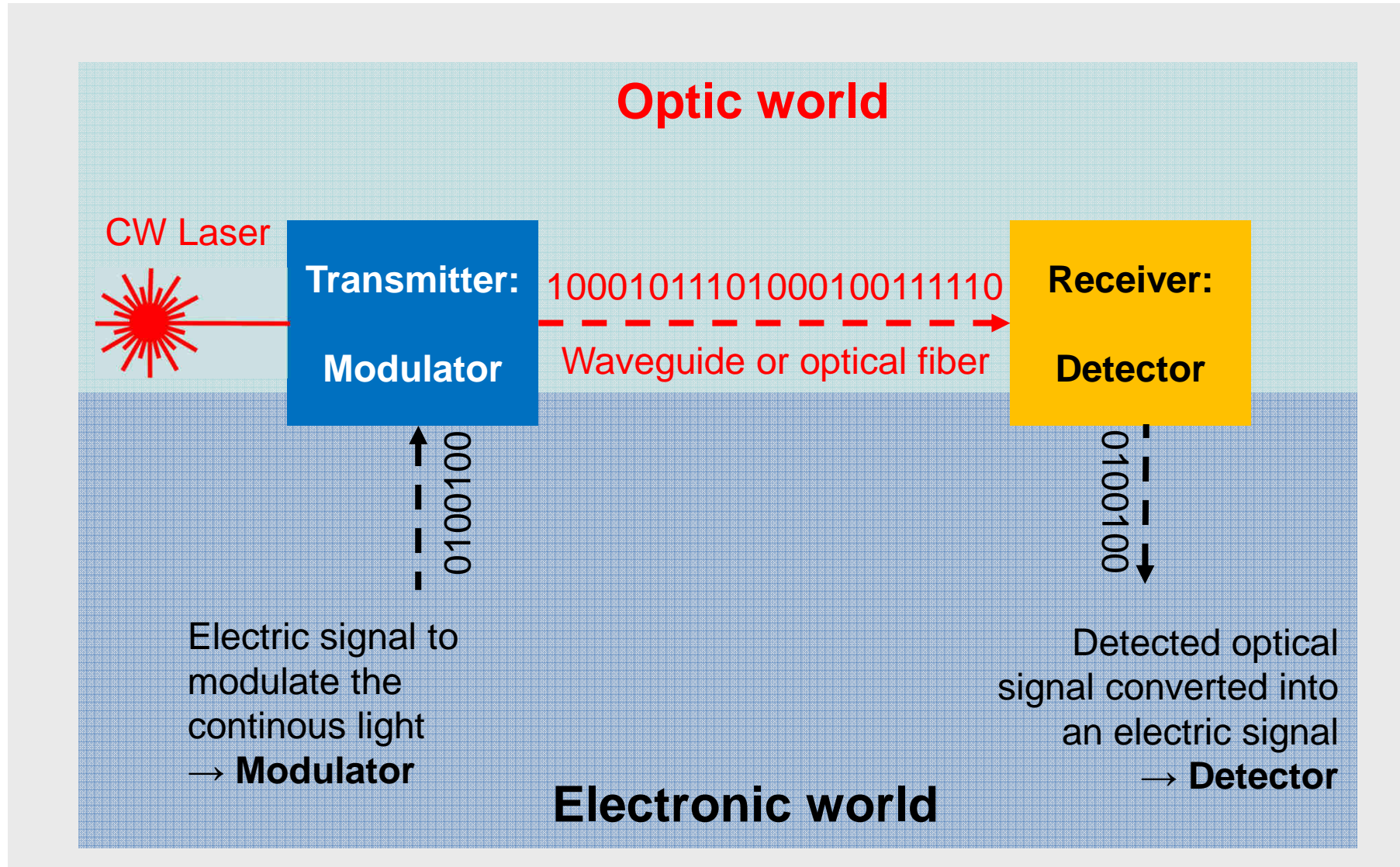
Technological compatibility at least in parts demonstrated:

Graphene on
300 mm wafer

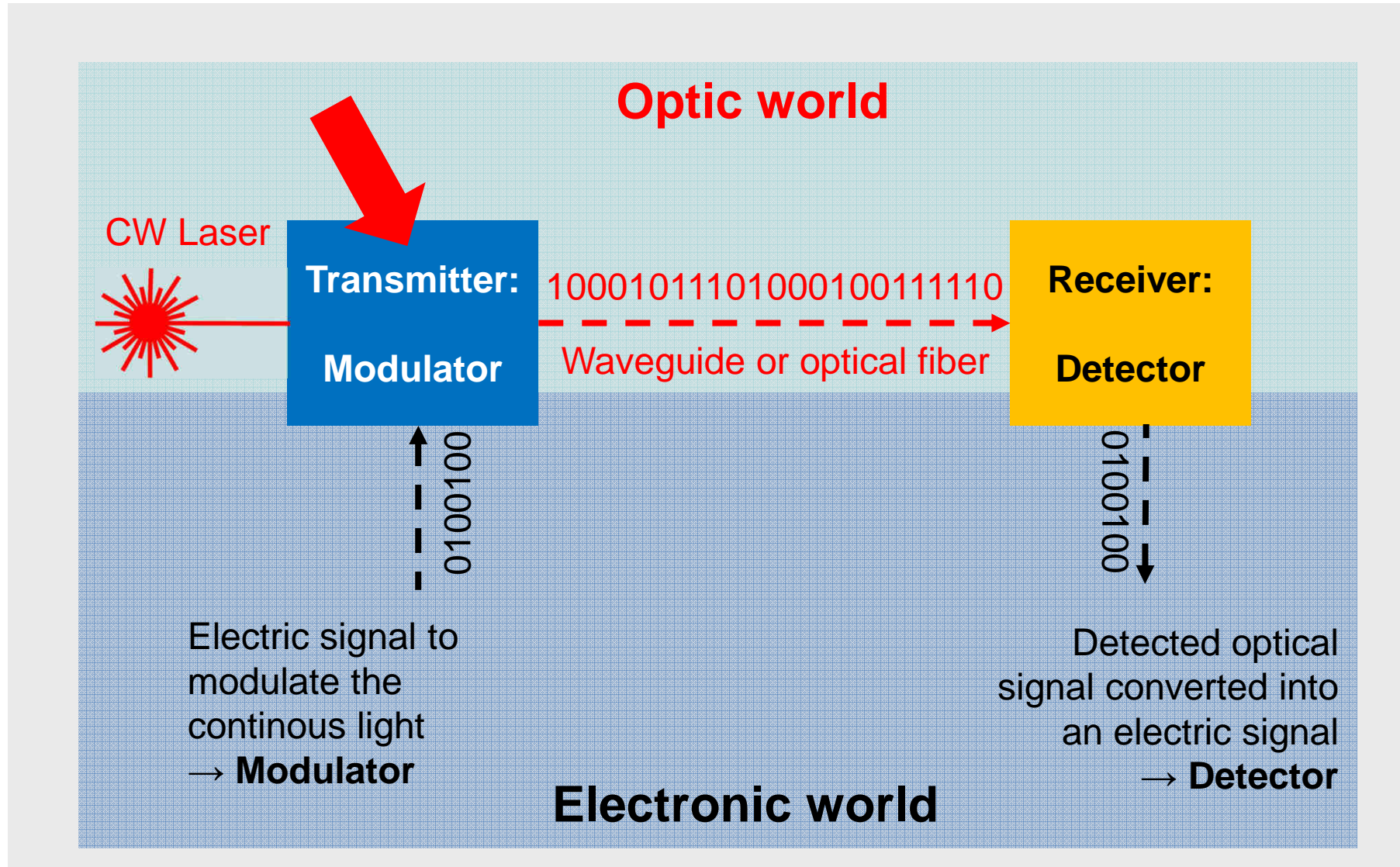


- Growth on 12 inch wafer size demonstrated
- Si integration feasible
- Thermally robust (at least to 300°C)

Optical communication schematic

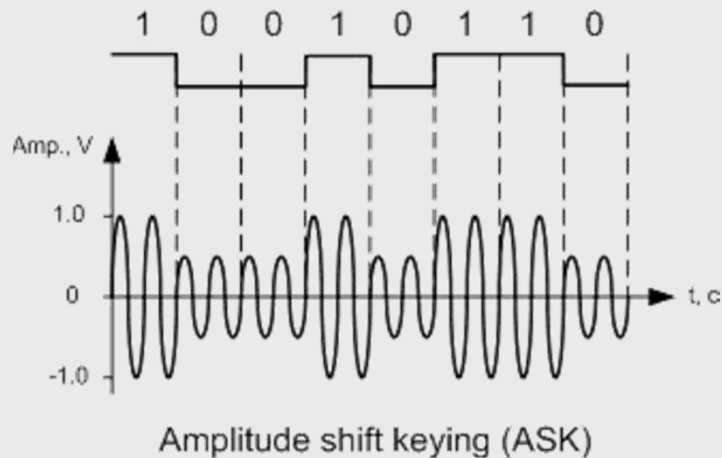


Optical communication schematic



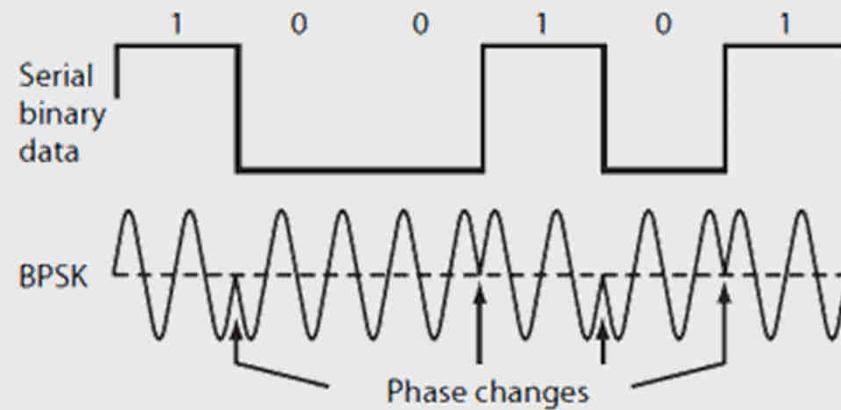
Transmitter: Phase vs. amplitude modulation

Amplitude shift keying ASK



- Simple System
- For low data rates / short distance

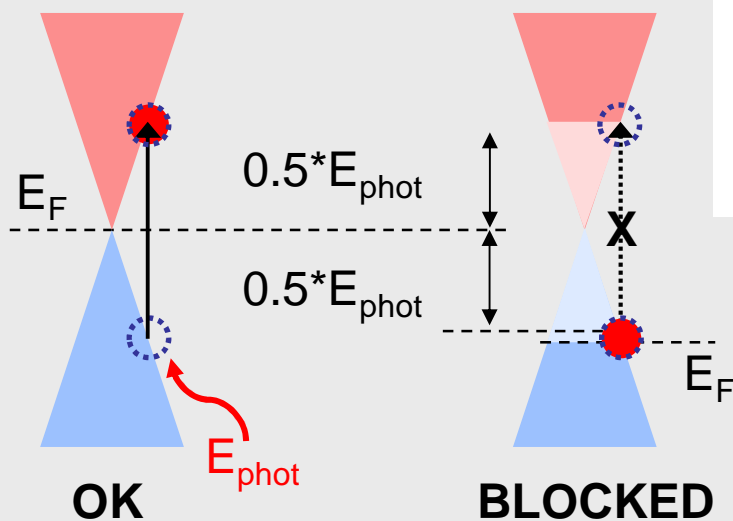
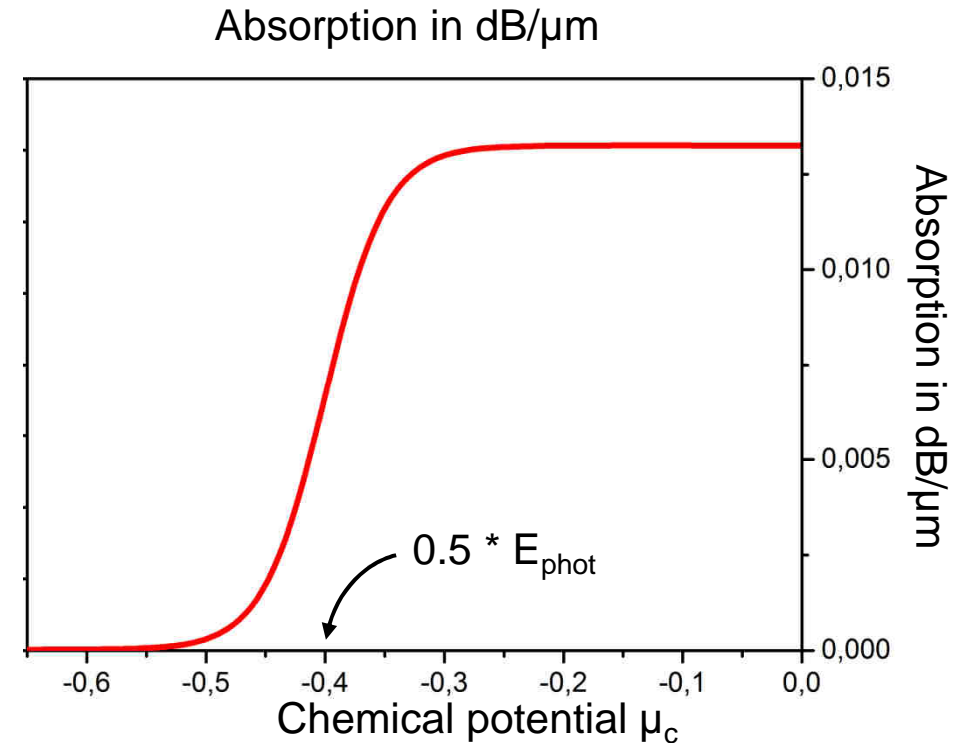
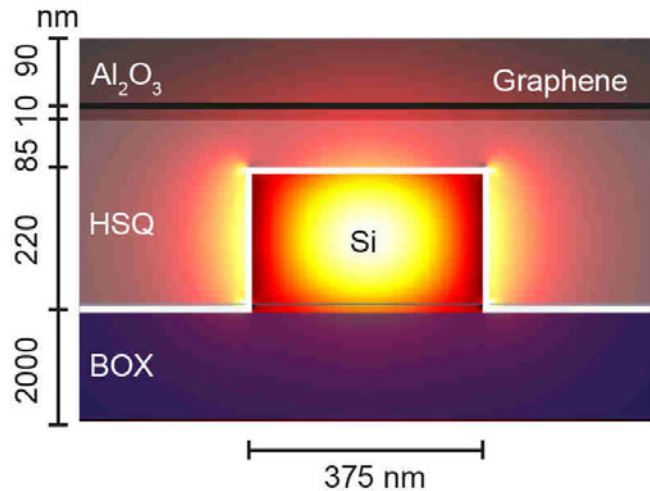
Binary phase shift keying BPSK



- Complex System
- For high data rates / long distance

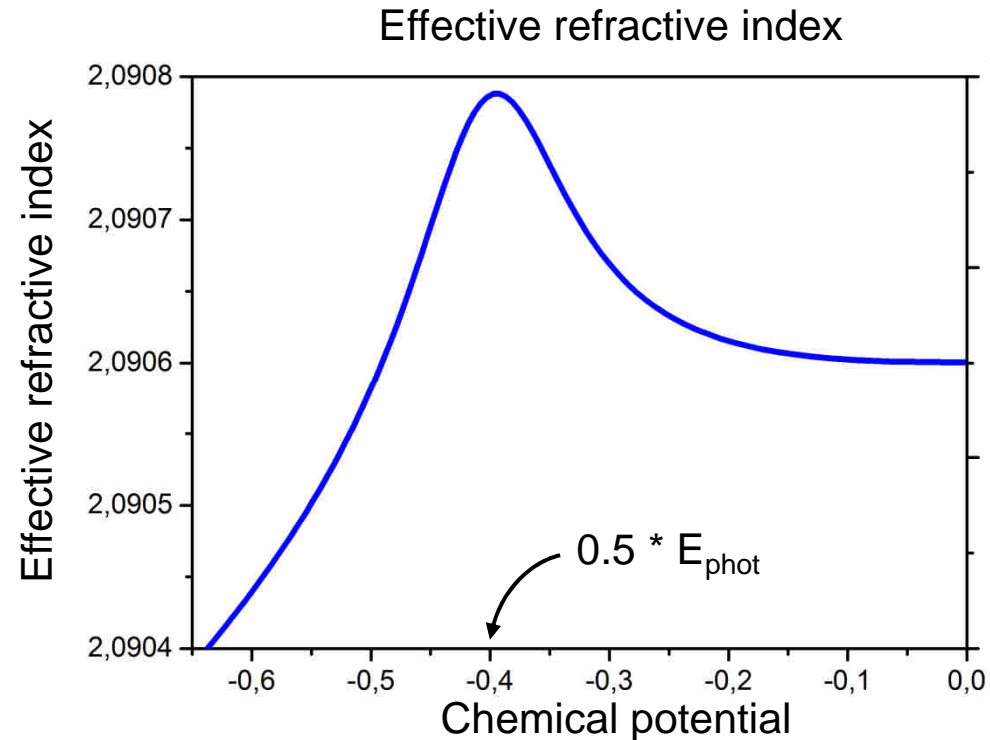
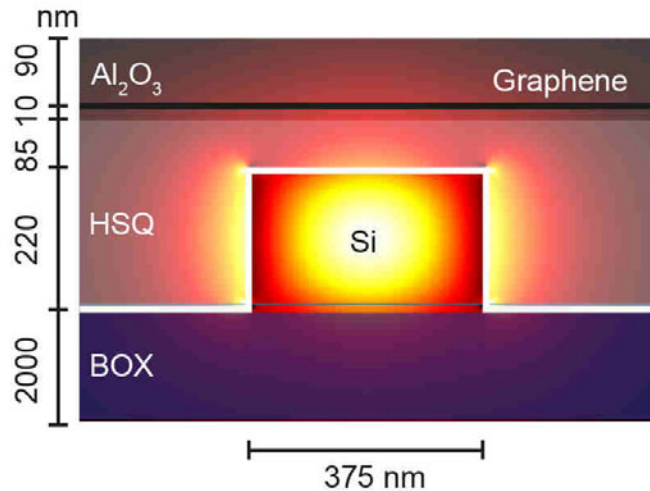
2 modulator operation principles.

Simulation of the absorption on Si waveguide



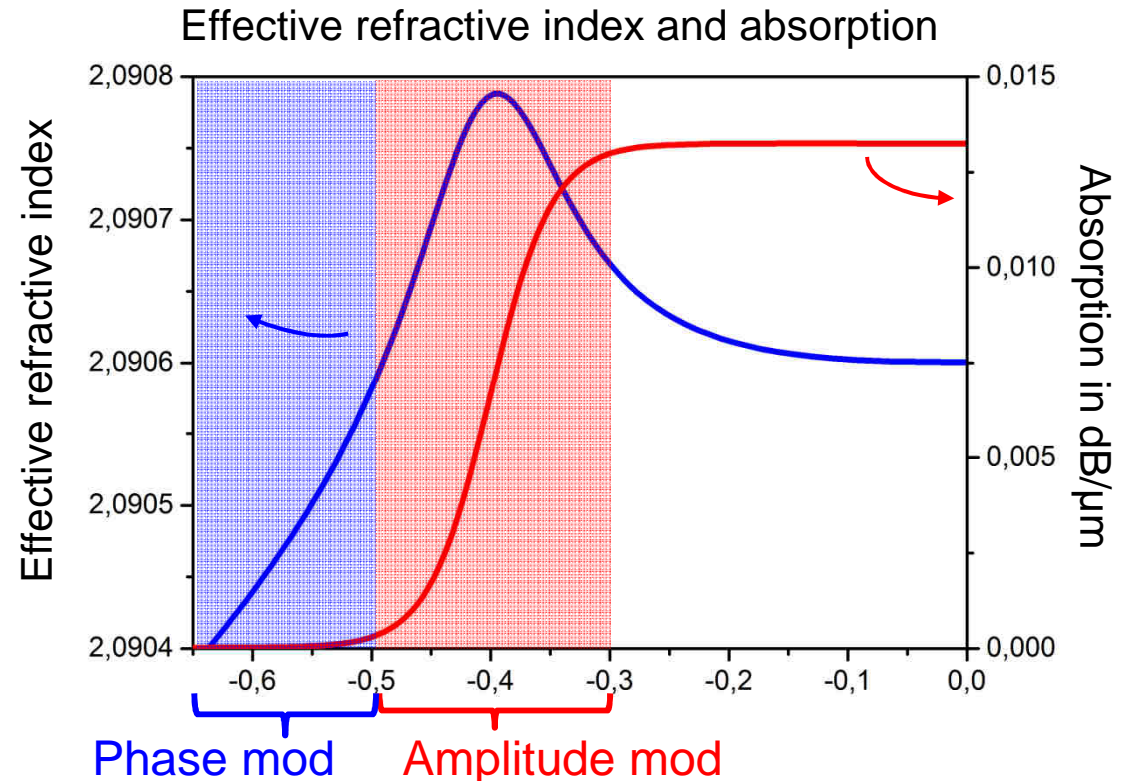
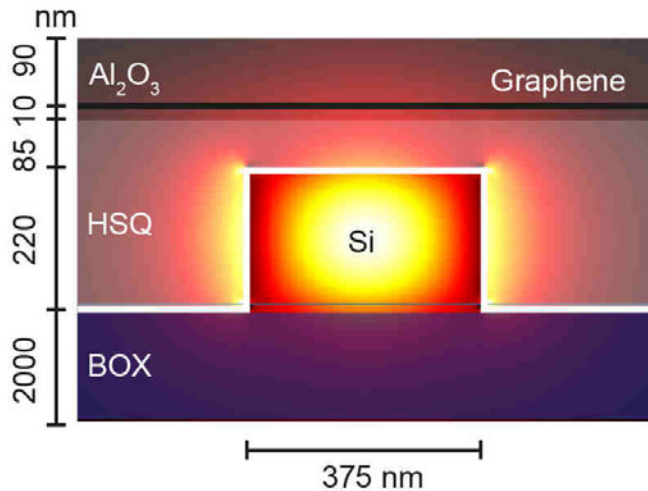
- $\lambda = 1550 \text{ nm} \rightarrow E_{\text{phot}} = 0.8 \text{ eV}$
- For $|\mu_c| \geq 0.5 * E_{\text{phot}}$ states are blocked
→ graphene is transparent

Simulation of the refractive index on Si waveguide



- $\lambda = 1550 \text{ nm} \rightarrow E_{\text{phot}} = 0.8 \text{ eV}$
- Kramers-Kronig relates the absorption to the refractive index
 → **refractive index is a function of the electro chemical potential**

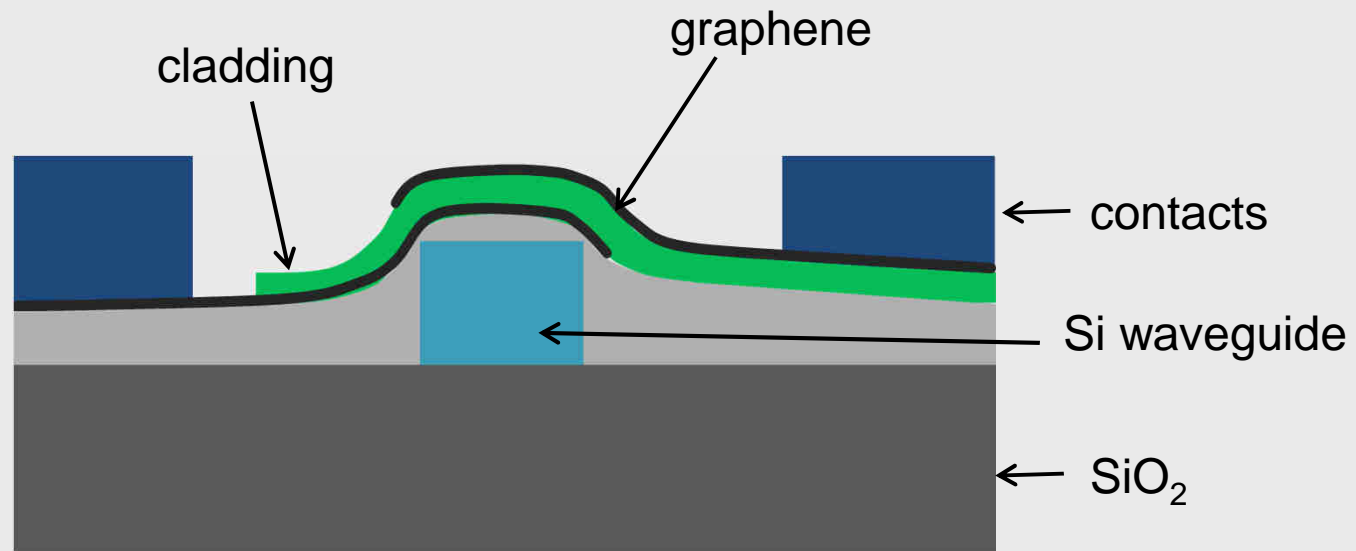
Simulation of absorption and refractive index on Si waveguide



- Refractive index and absorption depend on the chemical potential
- high mobility gives low absorption for $\mu < -0.4$ eV preferred for phase modulators.

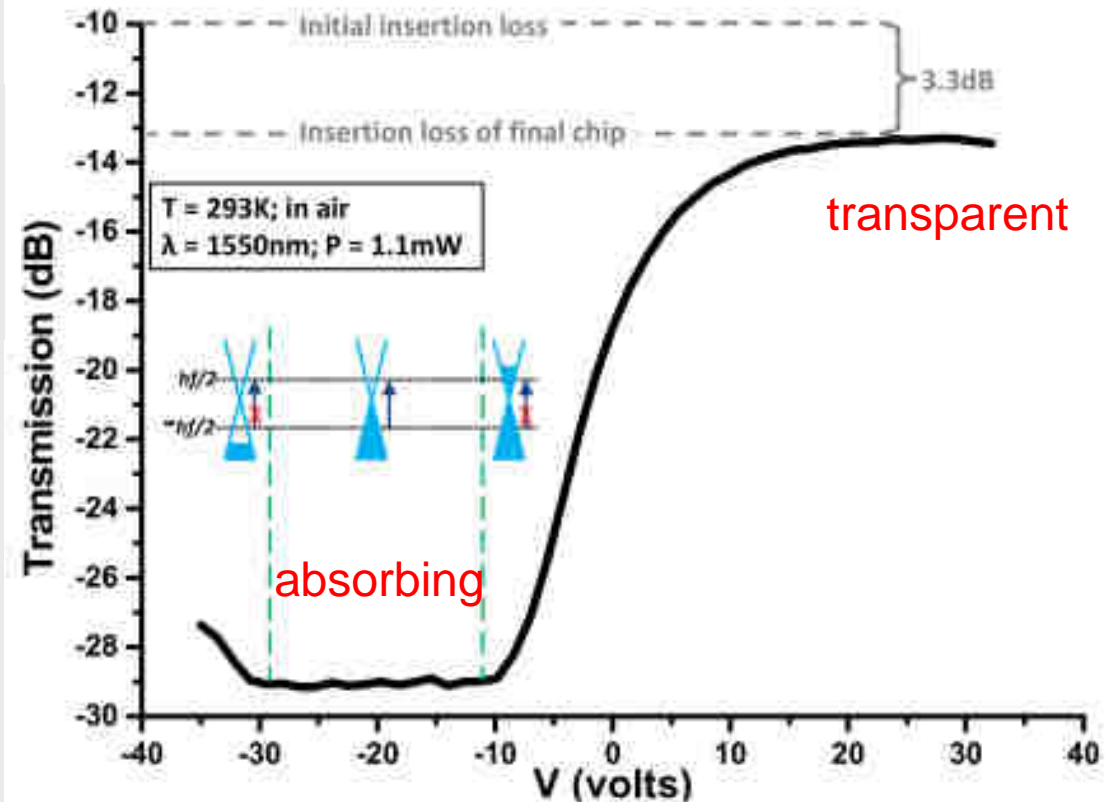
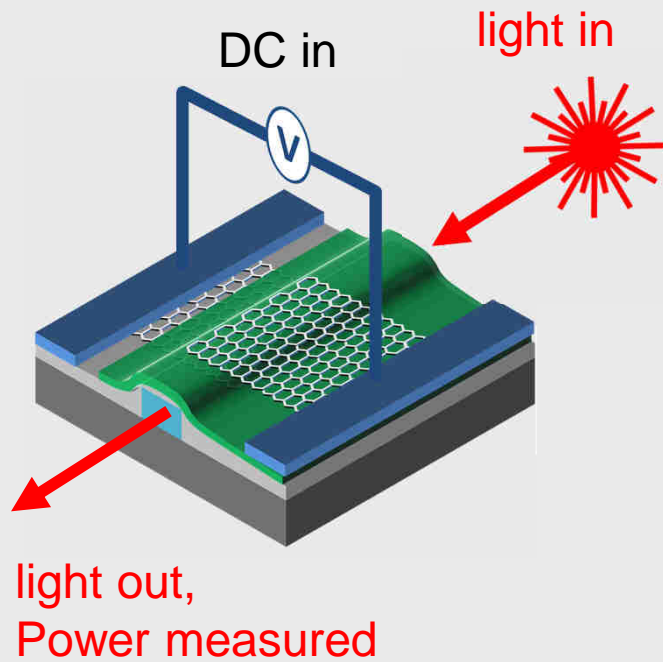
Phase and absorption modulator realizable

Absorption modulator schematic



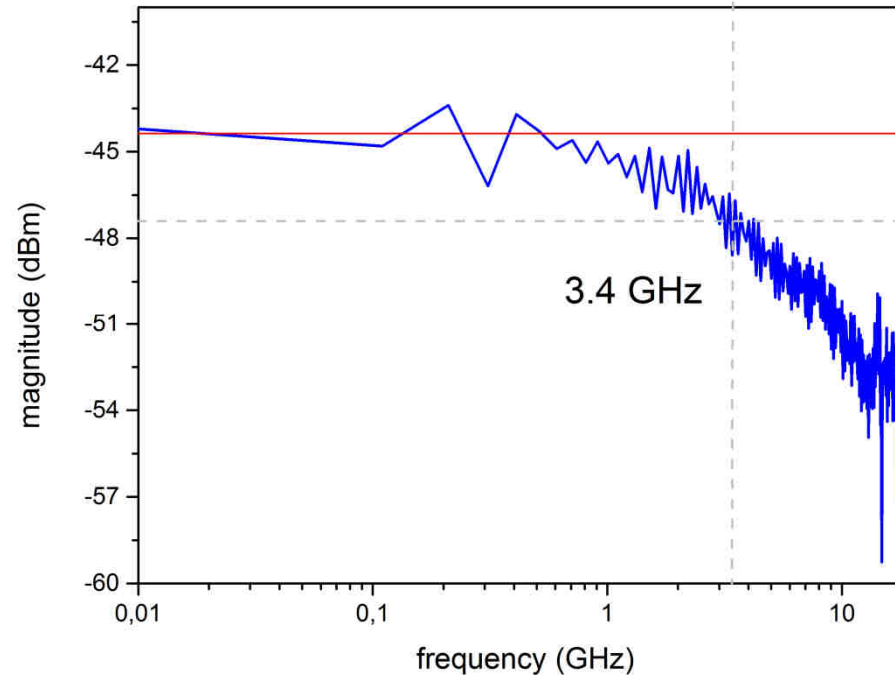
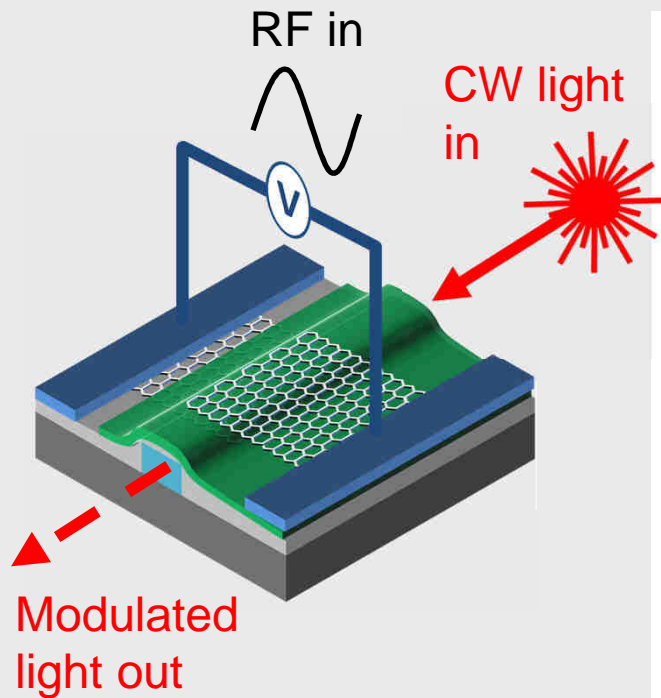
- SOI substrate 220 nm top Si
- Bottom electrode close to the waveguide surface
- Top electrode located in a distance of ~ 90 nm
- The lower electrode is adjusted between transparent and absorbing state

Absorption modulator DC



High modulation depth, low insertion loss.

Absorption modulator RF



Bandwidth limiting factors:

- Device geometry graphene electrode overlap $\sim 1.5 \mu\text{m}$
- Contact resistance
- No intrinsic limitation

30 GHz already demonstrated by the Lipson Group

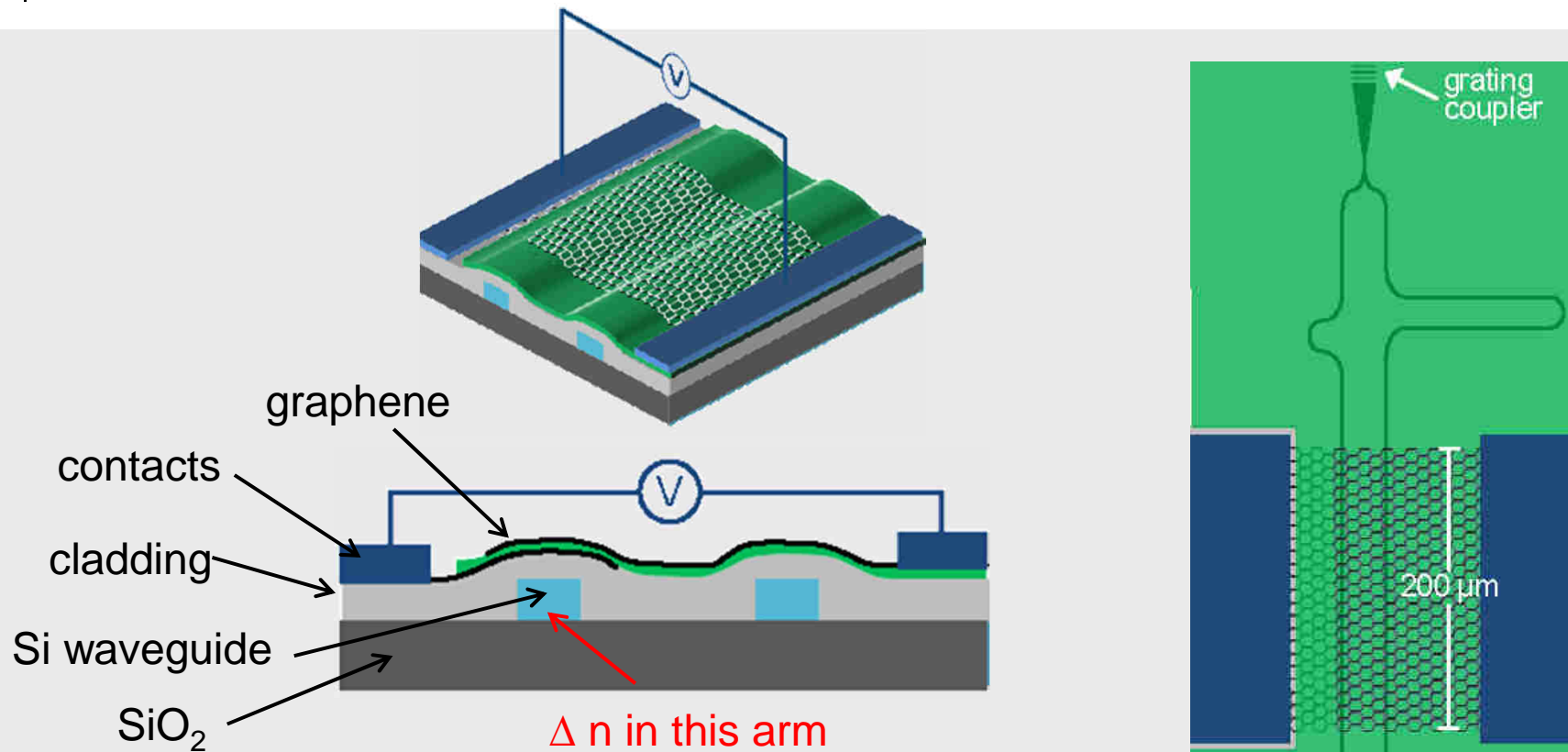
Absorption modulator comparison

	Graphene ¹	Graphene simulations	GeSi ²	Si (MZI) ³	(LiNbO) (~4500 €)
Modulation	16 dB	16 dB	6 dB	5.5 dB	20 dB
Insertion Loss	3 dB	<1dB	5 dB	4.2 dB	4 dB
Modulation / IL ratio	5	>15	1.2	1.3	5
Length	300 μm	<15μm	30 μm	5 mm	8 cm
Speed	3.4 GHz	>30 GHz	40 GHz	26.5 GHz	35 GHz

Performance already competitive to SOTA.

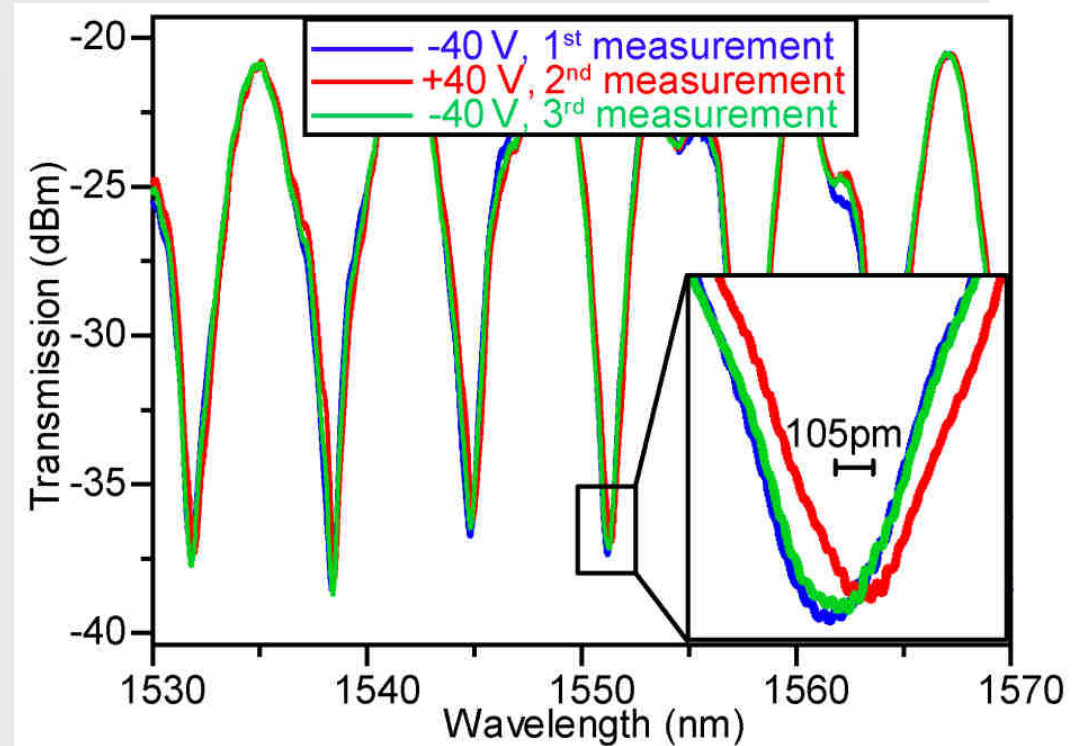
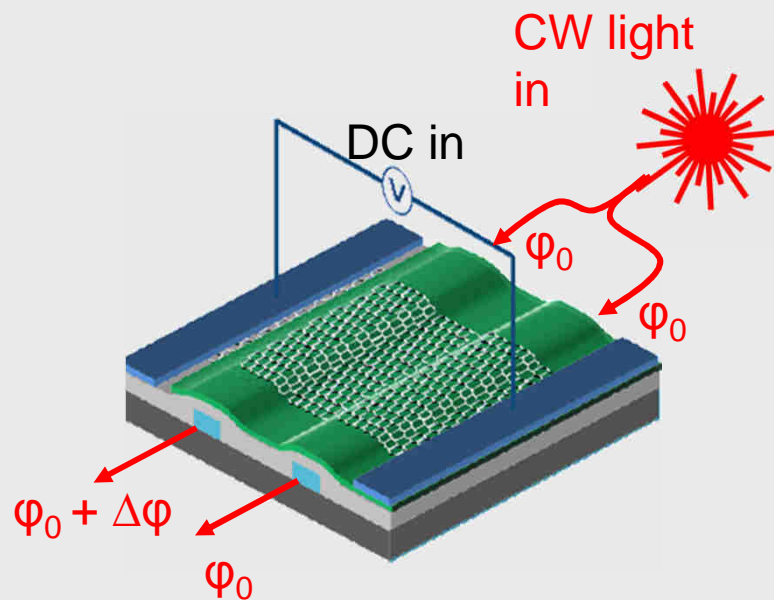
- 1) M. Mohsin et al. Optics Express 22, 15292 (2014)
- 2) D. Feng et al. Optics Express 20, 2224 (2013)
- 3) X. Tu et al. Optics Express 21, 12776 (2013)

Phase modulator schematic



- SOI substrate 220 nm top Si
- Bottom electrode close to the waveguide surface
- Top electrode located in a distance of ~ 90 nm
- The refractive index of the lower electrode is adjusted

Phase modulator DC measurement



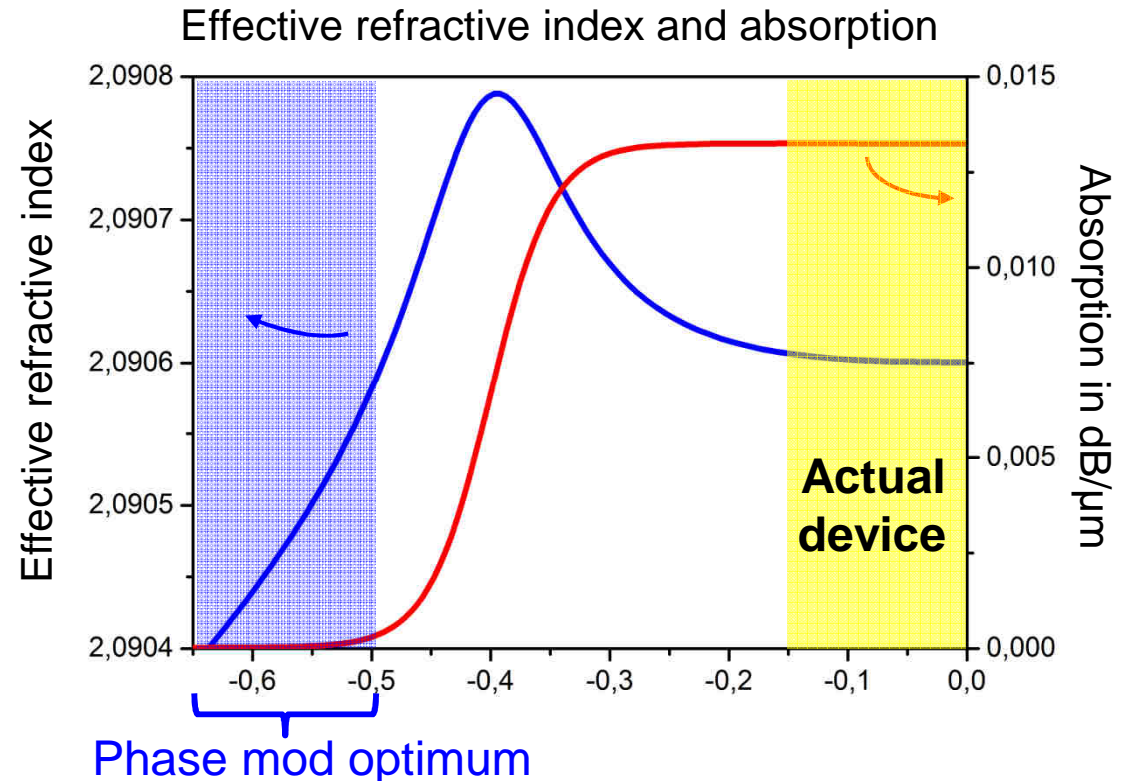
Phase shift observed, prove of concept.

Explanation of the results

The device was operated in the yellow shaded area.

Problems there:

- High absorption
- Small change of the refractive index



Solution: doping of the device to operate at optimum

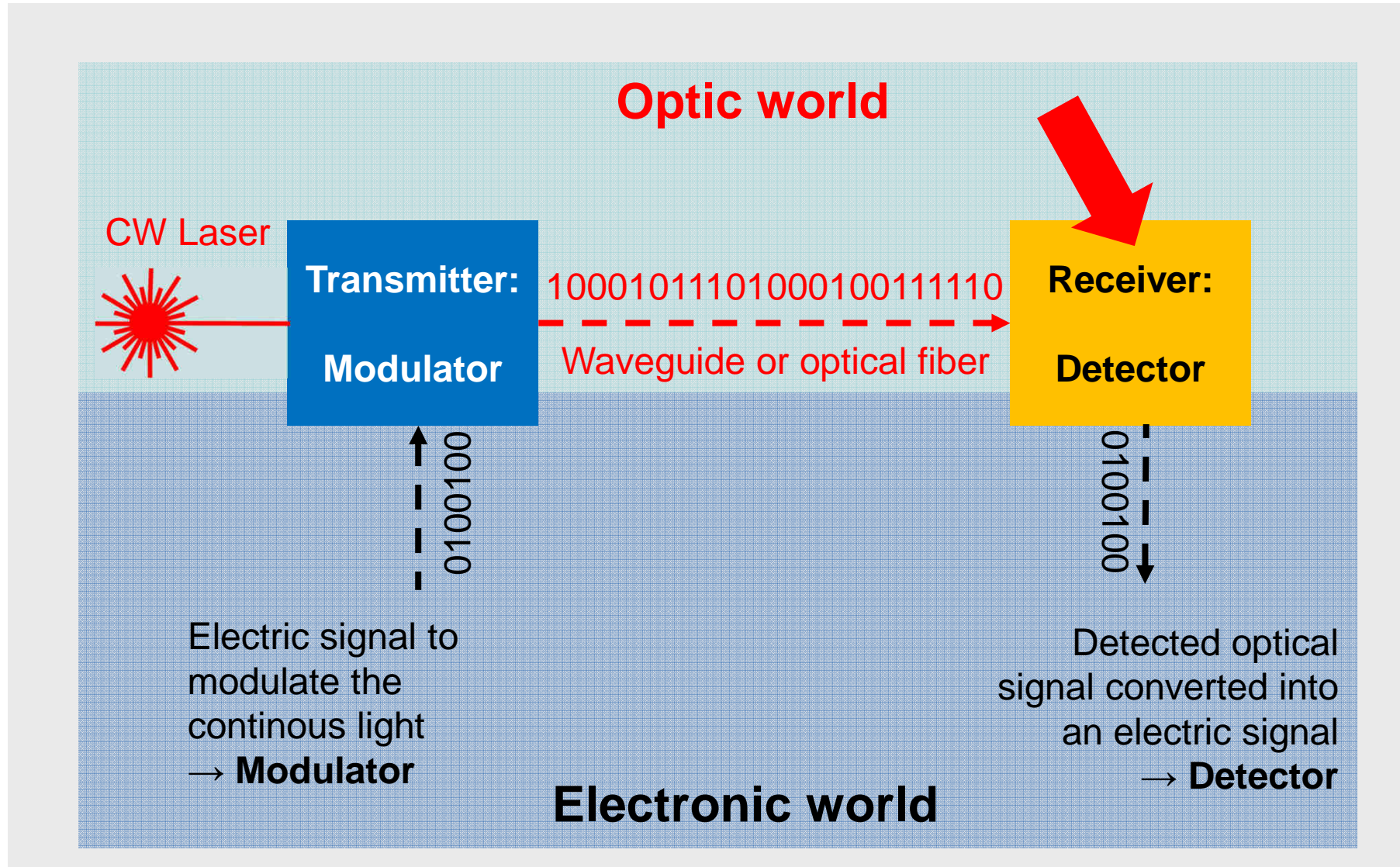
Phase modulator comparison

	Graphene ¹	Graphene Simulations ¹	SISCAP ²	Si depletion ³	(LiNbO) (~4500 €)
$V_{\pi}L$ (Vcm)	30	0.05	<0.2	2.5	~30
Insertion Loss α (dB/cm)	100	<170	65	11	0.6
$V_{\pi}L\alpha$	3000	<8.3	13	28.5	20

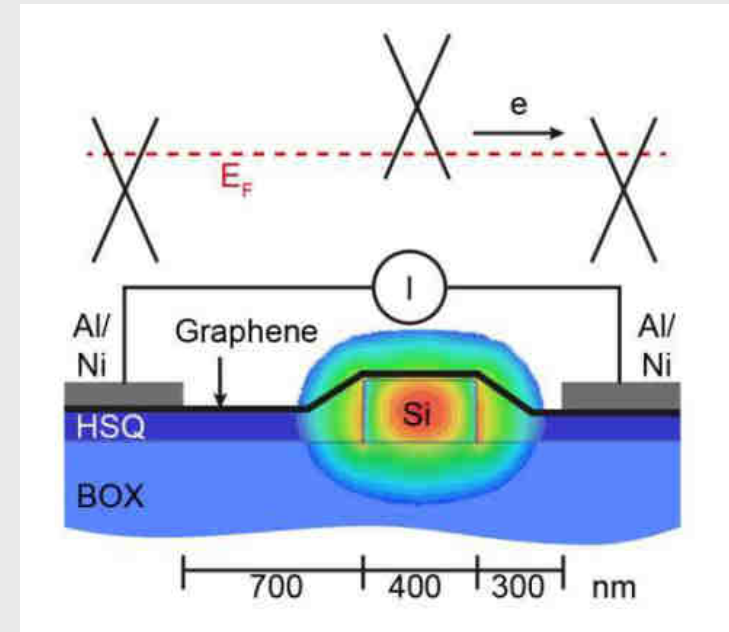
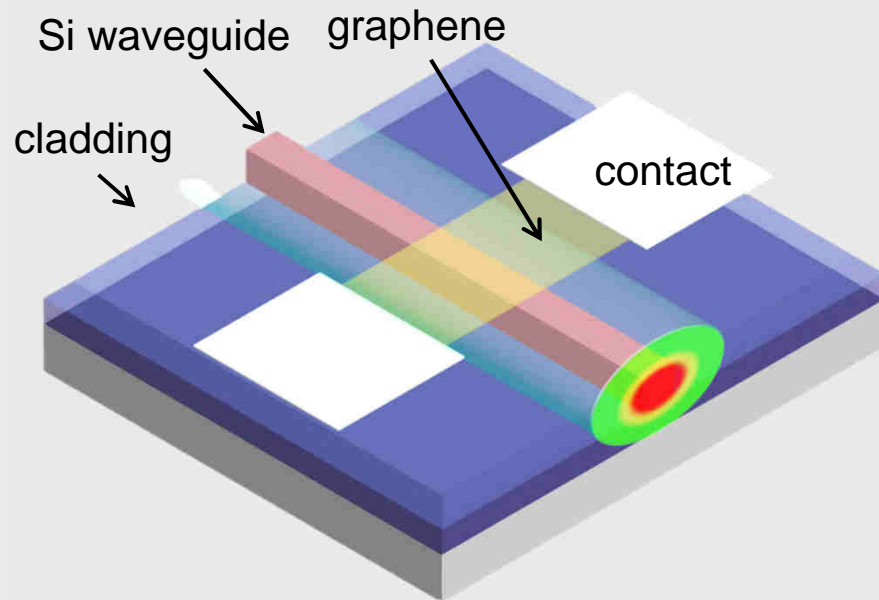
- Operation demonstrated, results far behind SOTA
- Excellent performance expected for high mobility (> 2000 cm²/Vs) and high doping levels > 0.5 eV

- 1) M. Mohsin et al. Scientific Reports 5,10967 (2015)
- 2) Webster et al. IEEE Group IV conf (2014)
- 3) Xiao et al. Optics Express 21, 4116 (2013)

Optical communication schematic

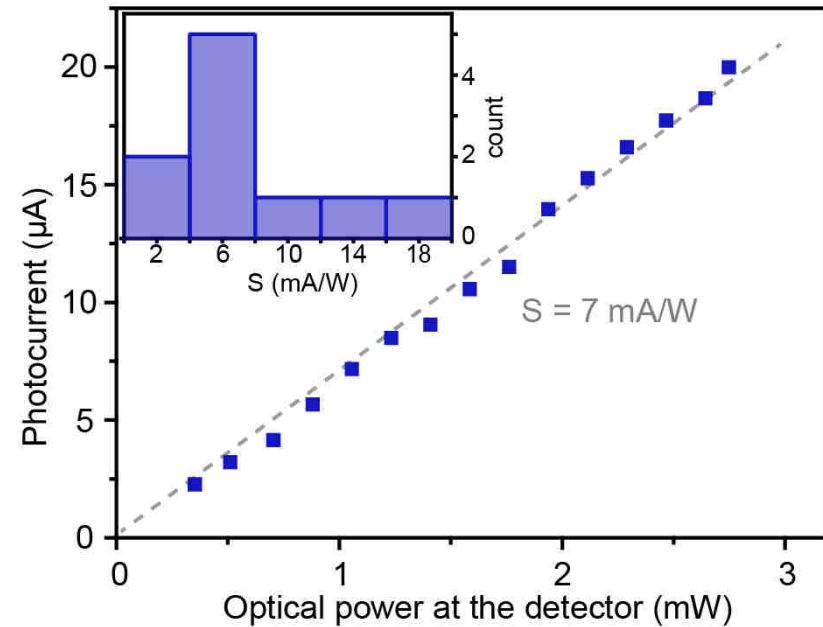
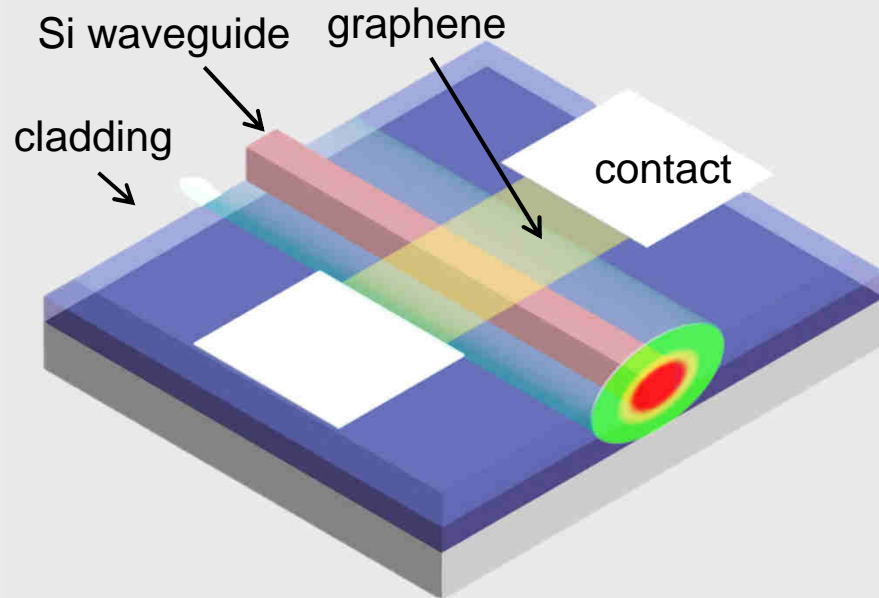


Photodetector schematic



- Graphene on Silicon (SOI) waveguide (for $\lambda = 1550$ nm).
- Graphene absorption $\sim 35\%$ for $l = 30\mu\text{m}$.
- CVD grown mono layer graphene (large scale, no flakes).
- Asymmetric contact scheme for net current flow.
- Measured in air and at RT

Bias free response

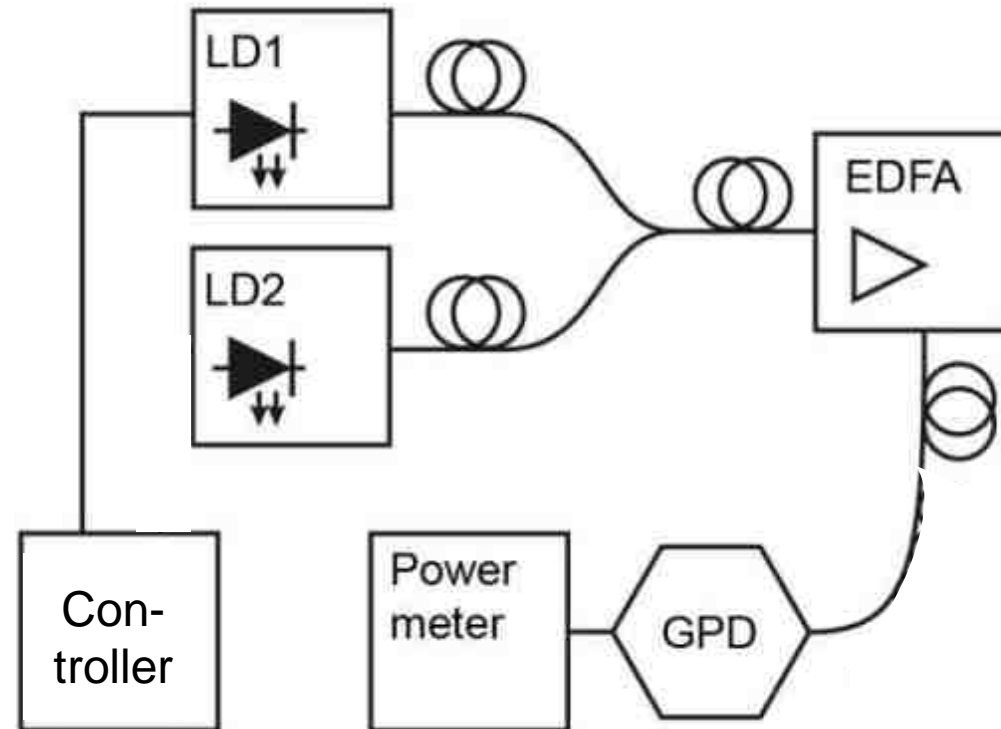


- 10 detectors on one die
- Linear dependency on optical power
- Extrinsic $S = 2..17 \text{ mA/W}$ without bias
- Intrinsic $S \sim 20...160 \text{ mA/W}$
- Quantum efficiency up to 13 %

RF Measurement setup

Signal generation by a heterodyne setup:

- Two laser sources at f_1 and f_2 (around 1550 nm, ~193 THz)
- Beating frequency
 $f = f_1 - f_2$
- f is varied from 1...110 GHz by tuning one laser source



GPD = Graphene photodetector
 EDFA = Erbium doped fiber amplifier
 LD = Laser diode

Flat up to 70 GHz!

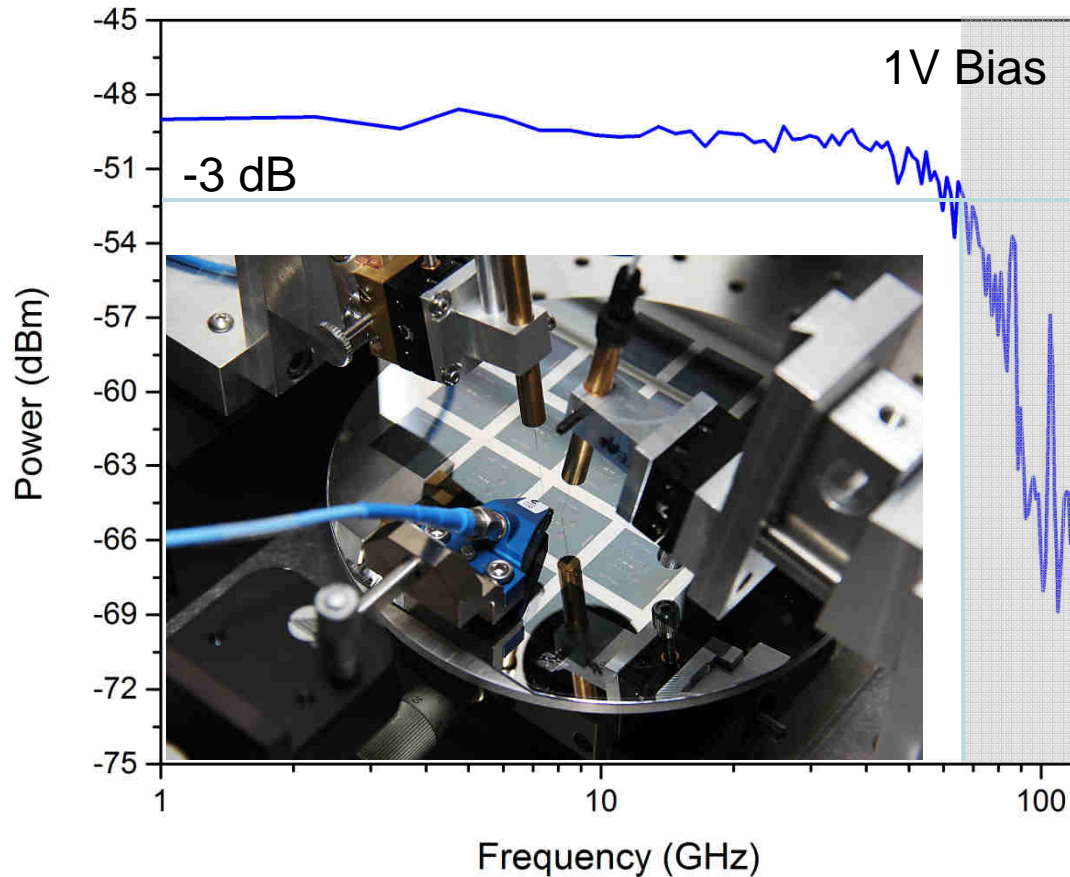
Measurement system designed up to 67 GHz

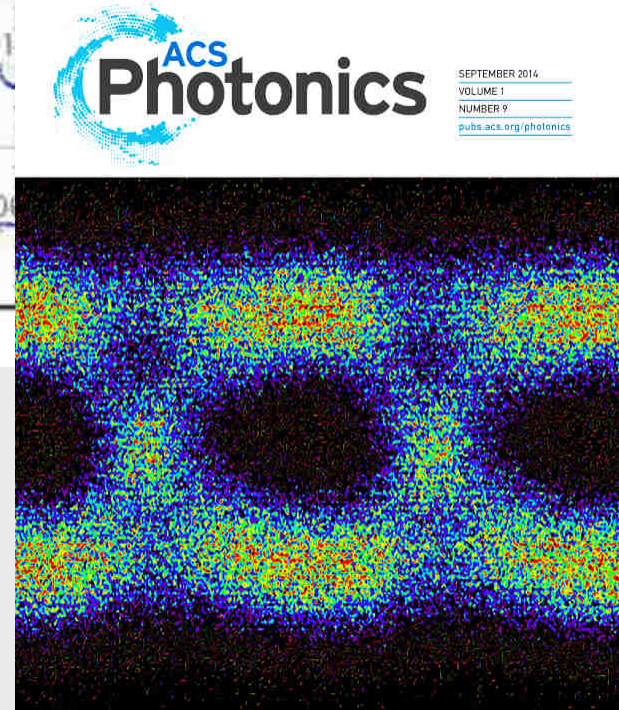
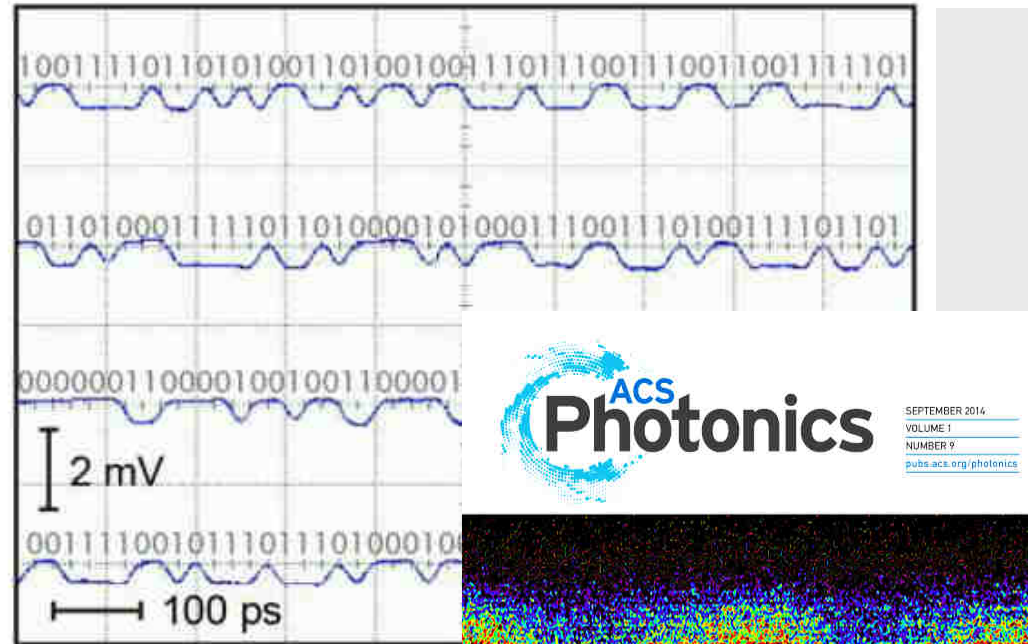
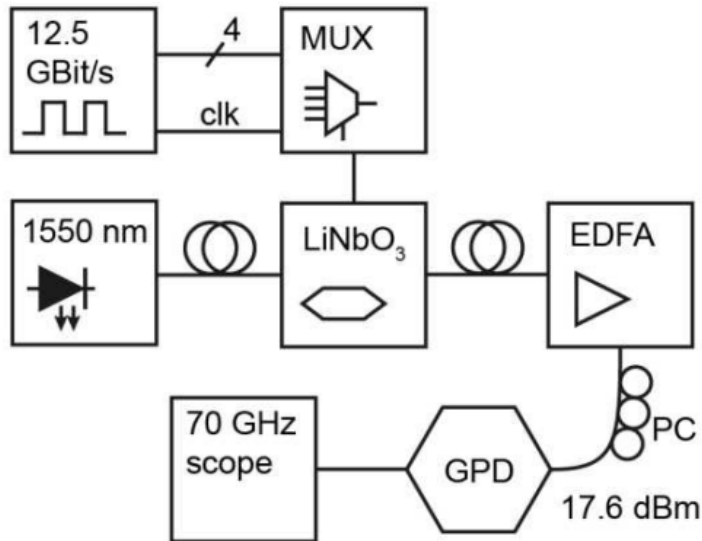
- Prober ~ 0.2 dB @ 67 GHz
- Cable 0.8 dB @ 67 GHz
- Bias Tee 0.5 - 1 dB @ 67 GHz

Significant contributions of the equipment to losses above 67 GHz.
Characteristic dominated by system.

Fabrication entirely on 6".

**Detector bandwidth larger than 70 GHz,
Datarate up to 150 GBit/s possible.**





- 50 GBit/s bit stream coupled to detector.
- Signal directly displayed at scope
- excellent signal integrity
- System rise time 9 ps (bandwidth 40 GHz)
- Eye diagram for 1 channel at 12.5 GHz

Extremely fast, but very low sensitivity.

Comparison to SOTA detectors

	Graphene ¹	Graphene potential	Ge ²	Ge-APD ³	InP ⁴	Phos-phorene ⁵
Data Rate GBit/s	50	> 150	40	10	160	3
Sensitivity A/W	0.01 .. 0.1	0.5	0.8 .. 1	10	0.6	0.7
Wafer-scale integration	Not perfect but feasible	OK	OK	OK	NO	Not yet

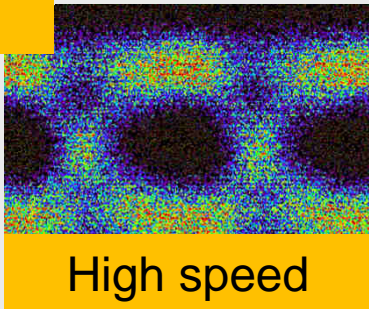
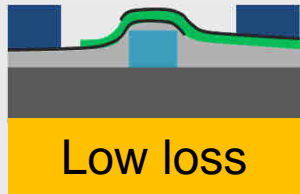
Graphene PDs become relevant for applications, if sensitivity is increased.

- 1) Schall et al. ACS Photonics 1, 781 (2014)
- 2) Vivien et al. Optics Express 20, 1096 (2012)
- 3) Virot et al. Nature Comm. 5, 4957 (2014)

- 4) Heinrich Hertz-Institute Berlin (2015)
- 5) Youngblood et al. Nature Phot. (2015)

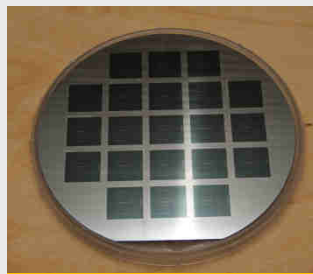
Paradigm shift – Requirements CHECK

Device requirements



Parameter	Det	Mod
High bandwidth	✓	✓
High sensitivity	✓	✓
High extinction ratio		✓
Low energy consumption	✓	✓
Low drive voltages	✓	✓
Low insertion loss		✓
Small footprint	✓	✓

Technological requirements



Parameter	
Manufacturing on large scale	✓
Integration possible	✓
Process compatibility	✓

300 mm growth

www.amo.de



OK



Not yet but feasible

The EO properties of graphene are very promising for optical interconnects:

- Graphene based photodetectors show ultrafast response; sensitivity is currently a major limitation.
- Graphene based amplitude modulators are already outperforming competing technologies in most parameters; the limited speed is not an intrinsic problem (30 GHz already demonstrated).
- Phase modulators based on graphene are promising from a theoretical point of view; large gap between experiment and theory.

▶ Graphene could become the missing link for the convergence of electronics and optics and enable the next paradigm shift.

AMO Graphene and Photonics
teams

Main collaborators:

Aixtron, Alcatel-Lucent, Graphenea,
Renato Negra, RWTH Aachen

Frank Koppens, ICFO

Roman Sordan, PMI

Thomas Mueller, TU Vienna

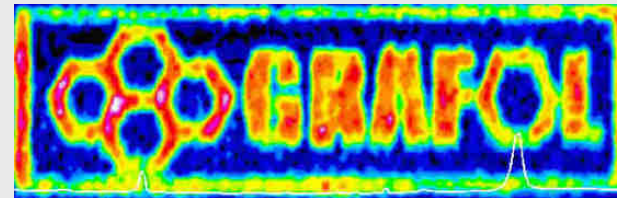
Christoph Stampfer, RWTH Aachen

Stephan Hofmann, UCAM

David Jimenez, UAB

Gianluca Fiori, Pisa

Gerd Bacher, Duisburg Essen





Thank you for your attention.